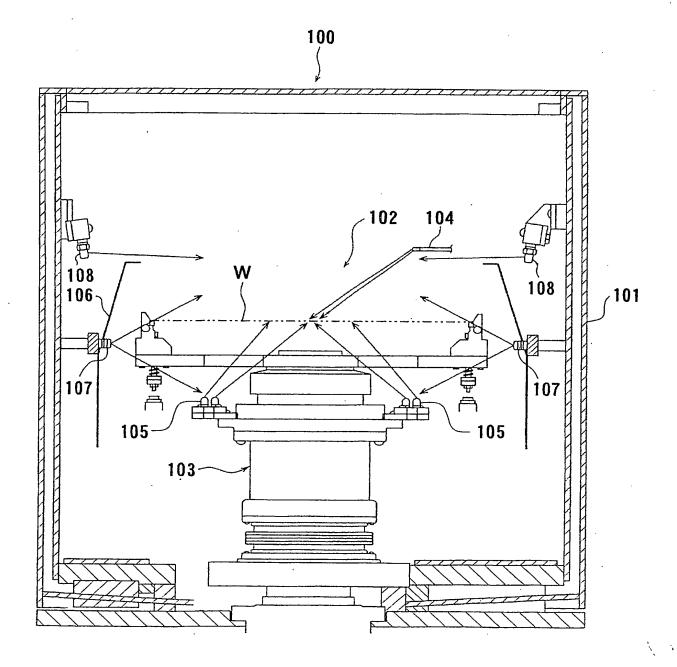
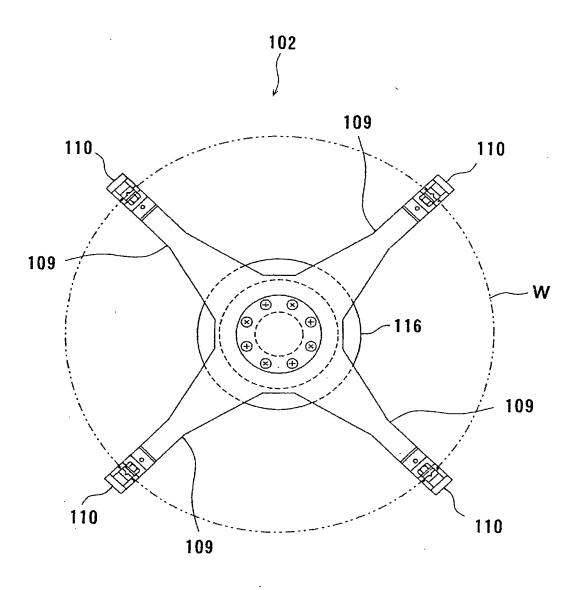
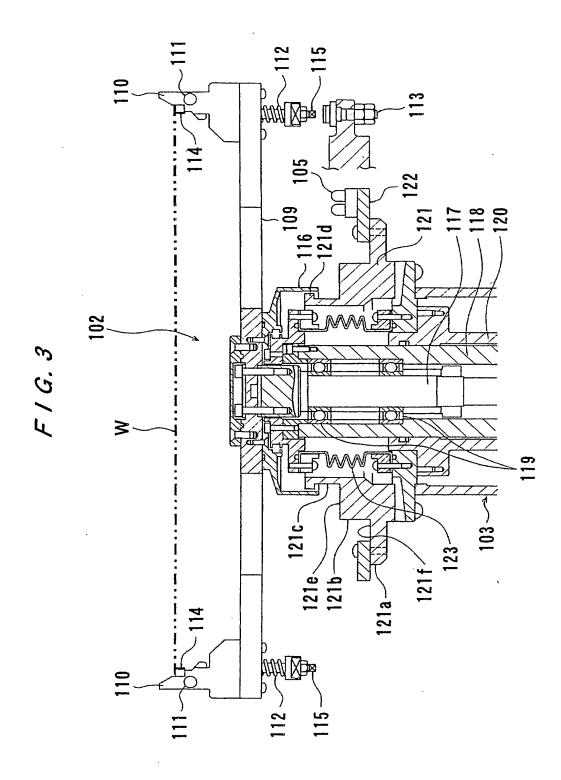
F / G. 1

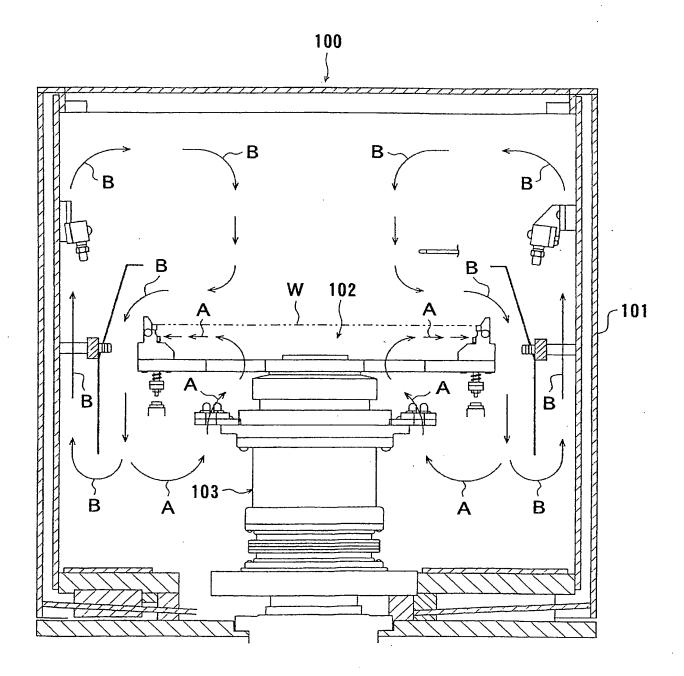




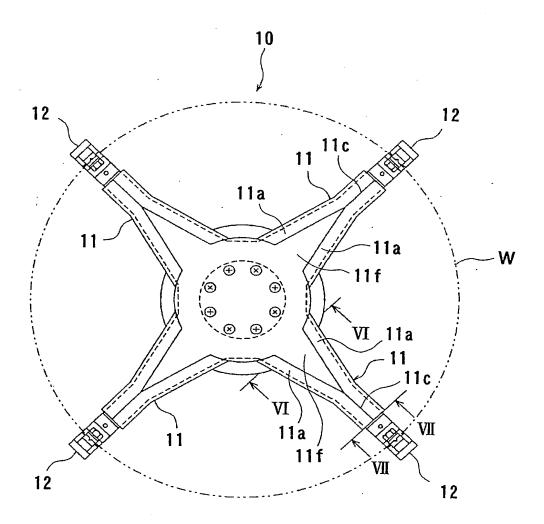




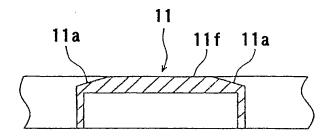
F / G. 4



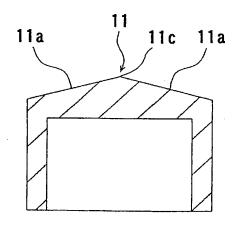
F / G. 5



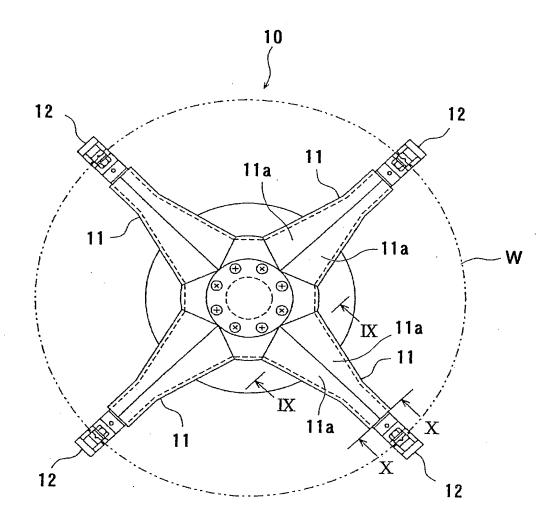
F / G. 6



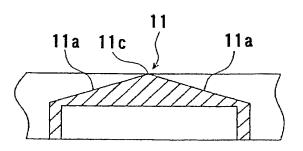
F / G. 7



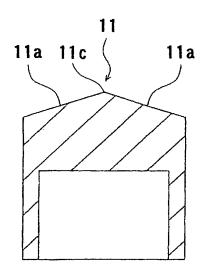
F 1 G. 8



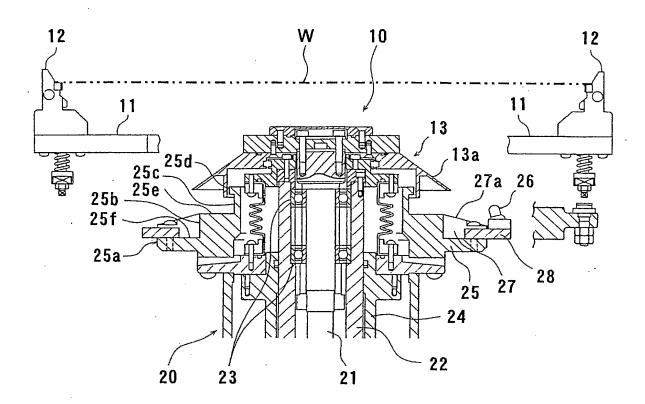
F 1 G. 9



F/G.10

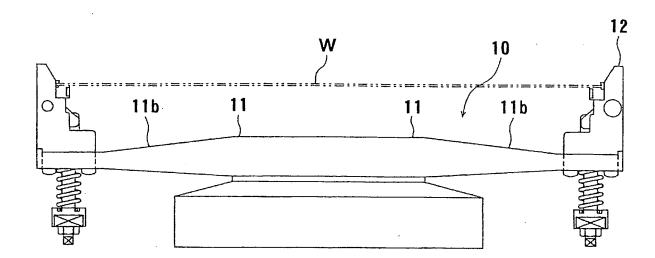


F / G. 11



PCT/JP2004/007560

F/G.12



		conventional example 1	conventional example 2	inventive example 1	inventive example 2
cleaning chamber	Step1	scrubbed using DIW or chemical liquid	scrubbed using a chemical liquid	scrubbed using DIW or chemical liquid	scrubbed using DIW or chemical liquid
	Step2	rinsed with DIW	rinsed with DIW	rinsed with DIW	rinsed with DIW
	Step3	spin-dried at a high speed (1500/minute)		spin-dried at a spin-dried at low speed (100/minute) (100/minute)	spin-dried at a low speed (100/minute)
	Step4			spin-dried at a high speed (1500/minute)	spin-dried at a low speed (200/minute)
	Step5				spin-dried at a high speed (1500/minute)
drving	Step1		rinsed with DIW	1	
chamber	Step2		spin-dried at a high speed (1500/minute)		1
Defect Coun	unt	264	65	99	14

F/G.1